



PATENT
Docket No. 360842008500

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In the application of:

Hiroyuki NIWA et al.

Serial No.: **10/069,136**

Filing Date: **February 22, 2002**

For: **POSITIVE TYPE RADIATION-
SENSITIVE COMPOSITION AND
PROCESS FOR PRODUCING
PATTERN WITH THE SAME**

Examiner: **Amanda C. WALKE**

Confirmation No.: **1671**

Group Art Unit: **1752**

AMENDMENT UNDER 37 CFR 1.111

Mail Stop AMENDMENT
Commissioner for Patents
2011 South Clark Place
Room 1B03, Crystal Plaza 2
Arlington, VA 22202

Sir:

In response to the Office Action dated March 24, 2004, please amend this application as follows:

The claim amendments begin on page 2.

The Remarks begin on page 9.